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IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Priority Application Serial No. 08/696,243
Priority Filing Date 08/13/96
Inventor Schuegraf
Assignee Micron Technology, Inc.
Priority Group Art Unit 2813
Priority Examiner M. Whipple
Attorney's Docket No. MI22-1098
Title: Semiconductor Processing Methods of Chemical Vapor Depositing SiO₂ on
a Substrate

PRELIMINARY AMENDMENT

To: Box PATENT APPLICATION
Assistant Commissioner for Patents
Washington, D.C. 20231

From: Lance R. Sadler (Tel. 509-624-4276; Fax 509-838-3424)
Wells, St. John, Roberts, Gregory & Matkin P.S.
601 W. First Avenue, Suite 1300
Spokane, WA 99201-3817

Sir:

Applicant preliminarily amends as follows:

AMENDMENTS

In the Specification

On page 1, before the "Technical Field" section, insert the
following section:

--RELATED PATENT DATA

This patent resulted from a continuation application of U.S. Patent
Application Serial No. 08/696,243, filed August 13, 1996, entitled
"Semiconductor Processing Methods of Chemical Vapor Depositing SiO₂